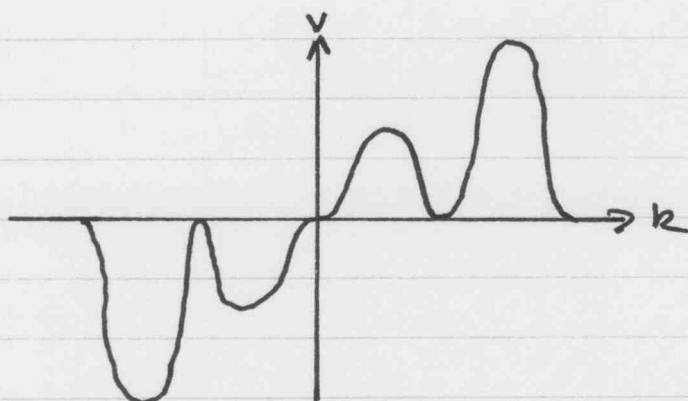
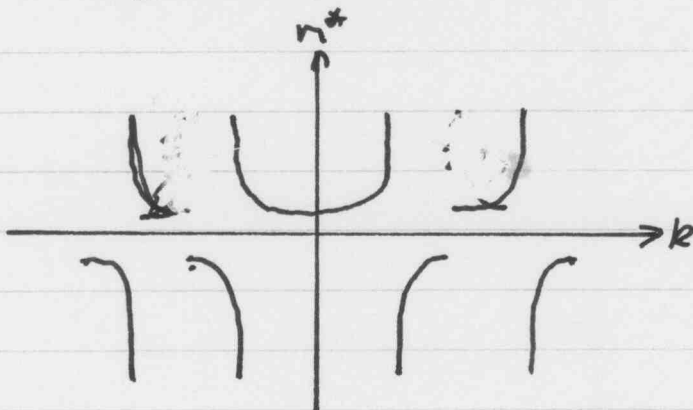


- 1 a i. When $k = n\pi/a$, the wavefunction of the electron fulfils the Bragg scattering criterion. Therefore, the wave cannot propagate, and so there is a disallowed state.
- ii. Close to the forbidden states, the evaluation of $|\psi|^2$ leads to two possibilities: that the electron is close to atoms and so 'sees' the potential well resulting in a lower energy state, or it is between the atoms and 'sees' the potential barrier between atoms resulting in a higher energy state. The electron is no longer sampling an average potential energy of the solid.

b i.



ii.



c i. As the valence band is fully occupied at 0K and only a small number of states become unoccupied by thermal, substitution or electromagnetic effects, it is easier ~~to~~ to consider the effect of removing electrons from the ^{full} valence band as being equivalent to adding holes to an empty valence band. We simply need to equate the two effects.

ii. If we remove an electron with a wave number k_e from the valence band, then the effect is to change the total wave number of all the electrons in this band by $-k_e$. Hence,

$$k_h = -k_e$$

Also, if the energy of the electron before removal was E_e , then the energy of the band is reduced by E_e , so

$$E_h = -E_e$$

Hence

$$v_h = \frac{1}{\hbar} \frac{\partial E_h}{\partial k_h} = \frac{1}{\hbar} \frac{\partial (-E_e)}{\partial (-k_e)} = \frac{1}{\hbar} \frac{\partial E_e}{\partial k_e} = v_e$$

iii. For effective mass,

$$m_h^* = \frac{\hbar^2}{\partial^2 E_h / \partial k_h^2} = \frac{-\hbar^2}{\partial^2 E_e / \partial k_e^2} = -m_e^*$$

iv. The overall shape of the E-k diagram is parabolic. Therefore, the gradient tends to increase with increasing Brillouin zone number. As the valence band is formed from a lower Brillouin zone, it will have a lower $\partial^2 E / \partial k^2$ and hence a greater effective mass.

- 2 a i. The Einstein postulate is demonstrated by the photoelectric effect. The maximum energy of electrons emitted from a metal surface in vacuum is linearly increases with photon frequency suggesting that $E = h\nu$.
- ii. Electron diffraction from a single crystal metal sample is evidence of the de Broglie postulate. When a beam of electrons is incident on such a sample, a peak in the reflected electron signal is measured at an angle corresponding to constructive interference of a wave where $\lambda = h/p$.

b $\frac{\partial \psi}{\partial t} = -j\omega \psi$

$$\frac{\partial \psi}{\partial x} = jk \psi$$

$$\frac{\partial^2 \psi}{\partial x^2} = -k^2 \psi$$

\therefore Substitution into the SE gives:

$$\frac{-\hbar^2}{2m} \cdot (-k^2 \psi) + V\psi = j\hbar \cdot (-j\omega \psi)$$

$$\therefore \frac{\hbar^2 k^2}{2m} + V = \hbar\omega$$

Now, $\hbar\omega = h\nu = E$ from Einstein. Also

$$\begin{aligned} \frac{\hbar^2 k^2}{2m} &= \frac{\hbar^2 (2a)^2}{\lambda^2 \cdot 2m} \\ &= \frac{h^2}{\lambda^2} \cdot \frac{1}{2m} \end{aligned}$$

From de Broglie

$$\frac{\hbar^2 k^2}{2m} = \frac{p^2}{2m} = \text{Kinetic Energy.}$$

Hence

$$\text{Kinetic Energy} + \text{Potential Energy} = \text{Total Energy.}$$

c) We have the independence, so

$$-\frac{\hbar^2}{2m} \frac{\partial^2 \psi}{\partial x^2} + V\psi = E\psi$$

Outside the well the only valid solution is $\psi = 0$.
Inside the well,

$$-\frac{\hbar^2}{2m} \frac{\partial^2 \psi}{\partial x^2} = E\psi$$

which has the general solution

$$\psi = A \sin(kx) + B \cos(kx)$$

but the boundary conditions near $\psi(0) = \psi(L) = 0$
so $B = 0$ and

$$\psi = A \sin\left(\frac{n\pi x}{L}\right)$$

Also

$$\int_0^L A^2 \sin^2\left(\frac{n\pi x}{L}\right) dx = 1$$

$$\therefore A = \sqrt{\frac{2}{L}}$$

$$\therefore \psi = \sqrt{\frac{2}{L}} \sin\left(\frac{n\pi x}{L}\right)$$

ii. Now

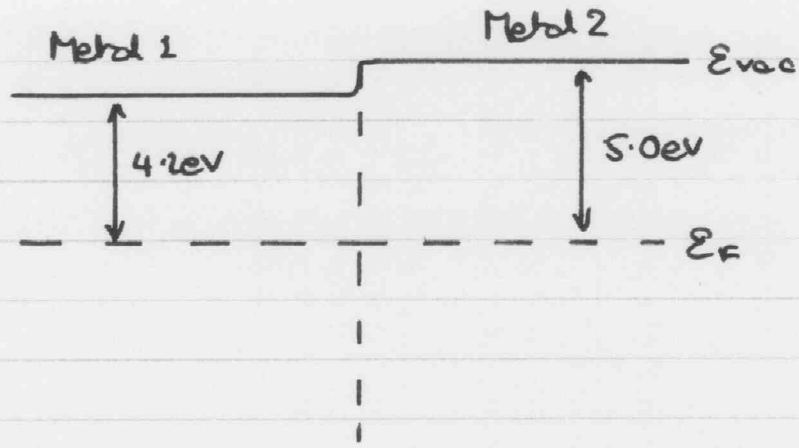
$$\begin{aligned} \frac{-\hbar^2}{2m} \frac{\partial^2 \psi}{\partial x^2} &= E\psi \\ \frac{-\hbar^2}{2m} \left[\frac{-n^2 a^2 \psi}{L^2} \right] &= E\psi \\ \therefore E &= \frac{n^2 a^2 \hbar^2}{2mL^2} \end{aligned}$$

Here, if $L = 5 \times 10^{-9} \text{ m}$ then for the ground state ($n=1$)

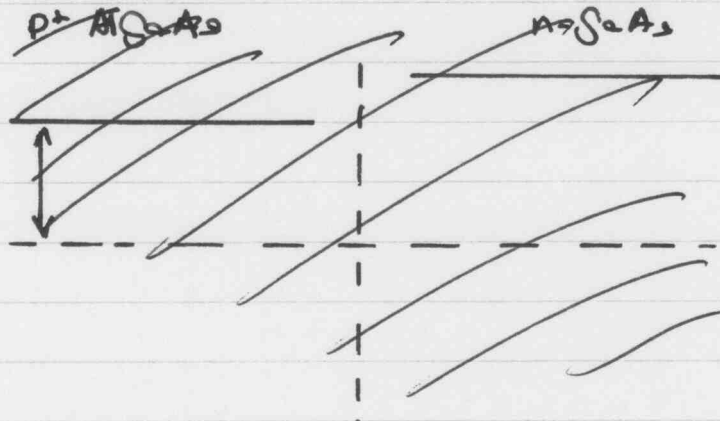
$$E = \frac{\pi^2 \cdot (1.055 \times 10^{-34})^2}{2.9 \cdot 109 \times 10^{-31} \cdot (5 \times 10^{-9})^2}$$

$$E = \underline{\underline{2.41 \times 10^{-21} \text{ J} = 15 \text{ meV}}}$$

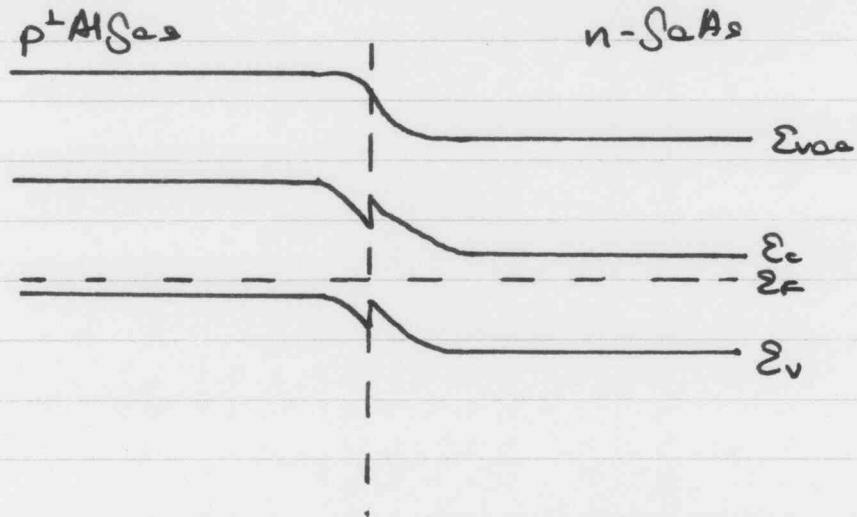
3 a i.



ii.



For $p^+ \text{AlGaAs}$, the E_F is close to the VB, so $\phi \approx 3.6 + 1.9 = 5.5 \text{ eV}$. For the GaAs , ϕ is just a bit bigger than the electron affinity, so $\sim 4.2 \text{ eV}$.



iii. The Se is p-doped, so

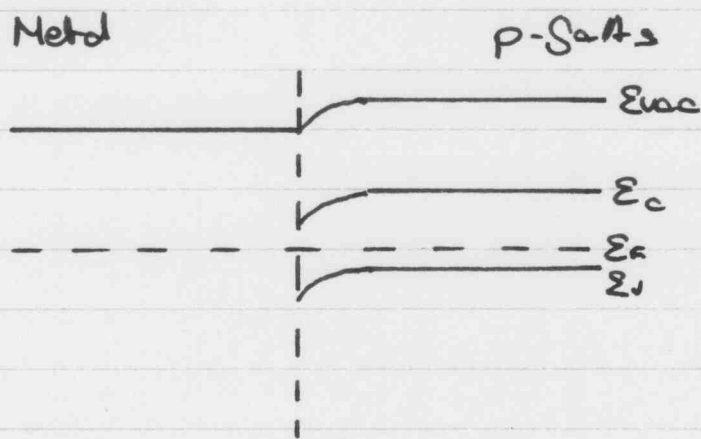
$$p \approx N_a \approx N_v \exp\left(\frac{-E_F}{kT}\right)$$

$$\therefore E_F = -kT \ln\left(\frac{N_a}{N_v}\right)$$

$$= -0.862 \times 10^{-4} \cdot 300 \ln\left(\frac{10^{21}}{6 \times 10^{24}}\right)$$

$$E_F = 0.22 \text{ eV}$$

Hence, $\phi = \chi + E_g - E_F = 4.0 + 0.67 - 0.22 = 4.45 \text{ eV}$



b i. ~~$n = N_c \exp\left(\frac{E_F - E_c}{kT}\right) \approx N_D$~~

~~$$\therefore -E_F + E_c = -kT \ln\left(\frac{N_D}{N_c}\right)$$~~

~~$$+ E_F = -kT \ln\left(\frac{N_a}{N_v}\right)$$~~

~~$$\therefore E_c = -kT \left(\ln\left(\frac{N_D}{N_c}\right) + \ln\left(\frac{N_a}{N_v}\right) \right)$$~~

~~$$E_c = -0.862 \times 10^{-4} \cdot 300 \left(\ln\left(\frac{N_D}{N_c}\right) + \ln\left(\frac{N_a}{N_v}\right) \right)$$~~

$$b \quad i \quad n = N_c \exp\left(\frac{E_F - E_c}{kT}\right) \quad p = N_v \exp\left(-\frac{E_F}{kT}\right)$$

$$\therefore np = n_i^2 = N_c N_v \exp\left(-\frac{E_c}{kT}\right)$$

$$\therefore E_c = -kT \ln\left(\frac{n_i^2}{N_c N_v}\right)$$

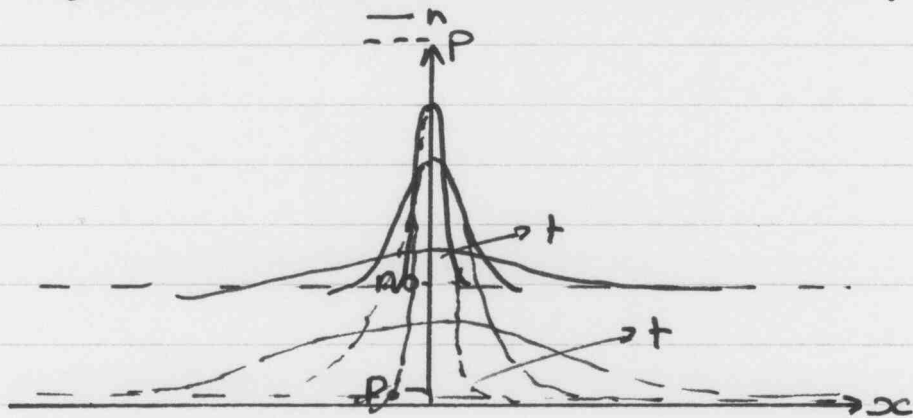
$$= -0.862 \times 10^{-4} \cdot 300 \ln\left(\frac{(10^{16})^2}{(10^{25})^2}\right)$$

$$\underline{E_c = 1.07 \text{ eV}}$$

$$ii. \quad n \approx N_D = 10^{24} \text{ m}^{-3}$$

$$p = \frac{n_i^2}{n} = \frac{(10^{16})^2}{10^{24}} = 10^8 \text{ m}^{-3}$$

iii. The laser will undergo creation of electrons and holes in equal numbers. These will diffuse away from the generation region and recombine.



$$iv. \quad p \approx N_A - N_D = 10^{24} \text{ m}^{-3}$$

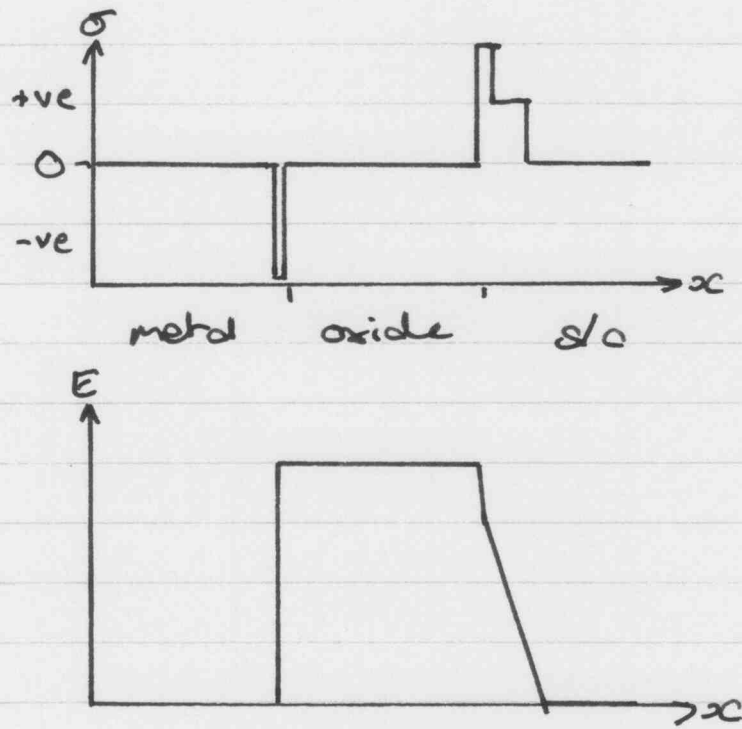
$$n = \frac{n_i^2}{p} = 10^8 \text{ m}^{-3}$$

4 a C_{max} occurs when there is no depletion region, so

$$C_{max} = \frac{\epsilon_0 \epsilon_{ox} A}{t_{ox}}$$

V_T is the point of onset of strong inversion when the opposite carriers to the semiconductor bulk build up on the semiconductor at the dielectric interface. V_T is -ve, so +ve charge is building up so this is an n-type semiconductor.

b



$$\sigma = \frac{C}{A} \cdot V_T$$

$$E_T = V_T / t_{ox}$$

$$\therefore \sigma = \frac{\epsilon_0 \epsilon_{ox}}{t_{ox}} \cdot E_T \cdot t_{ox}$$

$$E_T = \frac{\epsilon_0 \epsilon_{ox} \sigma}{\epsilon_0 \epsilon_{ox}}$$

c

$$\tau_{inv} = \frac{e n_0 t_{inv}}{p_0 e v_0}$$

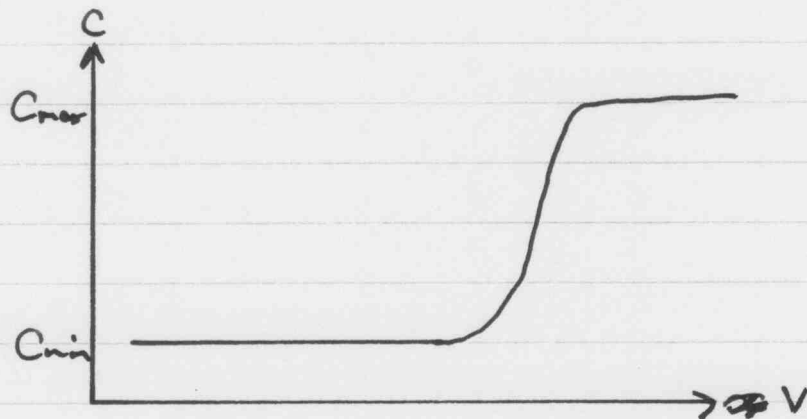
$$n_0 = N_D = 5 \times 10^{22} \text{ m}^{-3}$$

$$p_0 = \frac{n_i^2}{n_0} = \frac{(1.5 \times 10^{16})^2}{5 \times 10^{22}} = 4.5 \times 10^9 \text{ m}^{-3}$$

Take $t_{inv} \approx 5 \text{ ns}$ so

$$\tau_{inv} = \frac{1.602 \times 10^{-19} \cdot 5 \times 10^{22} \cdot 5 \times 10^{-9}}{4.5 \times 10^9 \cdot 1.602 \times 10^{-19} \cdot 10^5} = 0.56 \text{ s}$$

d



e

~~$$\sigma_T = \frac{C}{A} \cdot V_T$$~~

$$\sigma_T = \frac{C}{A} \cdot V_T$$

$$\sigma_T = \frac{\epsilon_0 \epsilon_{ox}}{t_{ox}} \cdot V_T$$

$$\therefore V_T = \frac{\sigma_T t_{ox}}{\epsilon_0 \epsilon_{ox}}$$

$\therefore V_T \propto 1/\epsilon_{ox} \Rightarrow \epsilon_{ox}$ can be used to control V_T .

f Subthreshold slope will increase.